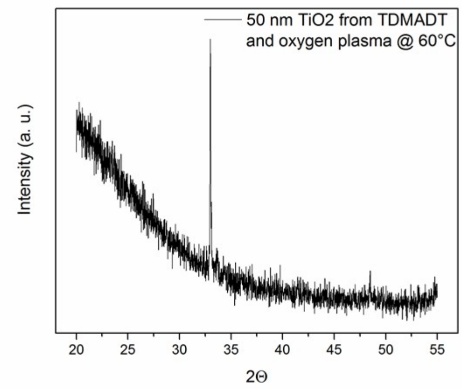
Electronic Supplementary Material (ESI) for Journal of Materials Chemistry C.

Supplementary Information



SI Fig. 1: Representative XRD pattern of a 50 nm TiO_2 *thin film on Si(100), deposited at 60 °C using TDMADT and oxygen plasma (150 ms, 200 W).*